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## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of: Hideki Fujiwara et al.

Application No.: National Phase of

PCT/JP2005/006134

Filed: Concurrently Herewith Art Unit: N/A

For: SILICON ELECTRODE PLATE FOR PLASMA Examiner: Not Yet Assigned ETCHING WITH SUPERIOR DURABILITY

(AS AMENDED)

## FIRST PRELIMINARY AMENDMENT

MS PCT Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

Dear Sir:

## INTRODUCTORY COMMENTS

Prior to examination on the merits, please amend the above-identified U.S. patent application as follows:

Amendments to the Specification begin on page 2 of this paper.

Remarks/Arguments begin on page 3 of this paper.